

ABSTRACT

In one aspect, provided is a cleaning agent composition for a substrate for a semiconductor device, the cleaning agent composition having excellent cleaning properties against ceria and being capable of reducing a temporal change in the solubility of ceria.

In one aspect, the present disclosure relates to a cleaning agent composition for a substrate for a semiconductor device, the cleaning agent composition containing a component A, a component B, a component C, and a component D,

the component A being sulfuric acid;

the component B being ascorbic acid;

the component C being at least one of thiourea and dithiothreitol; and

the component D being water.